

AMENDMENTS TO THE ABSTRACT:

Please amend the abstract as follows:

Abstract

A17
The batch projection regions 43 and 44 of ~~the~~ an electron beam projection mask are arranged so that pattern density may be equalized on the whole wafer surface.--

HAYES SOLOWAY P.C.

130 W. CUSHING ST.
TUCSON, AZ 85721
TEL 520 882 7623
FAX 520 882 7643

175 CANAL STREET
MANCHESTER, NH 03101
TEL 603 668 1400
FAX 603 668 8567